

Supplementary figures

to K.Grigras abstract "Annealed ALD TiN_x layers for through-silicon superconducting interconnects"

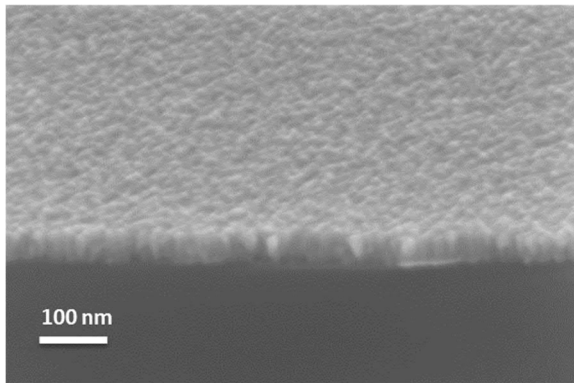


Figure 1. Tilted SEM view of 47 nm TiN layer

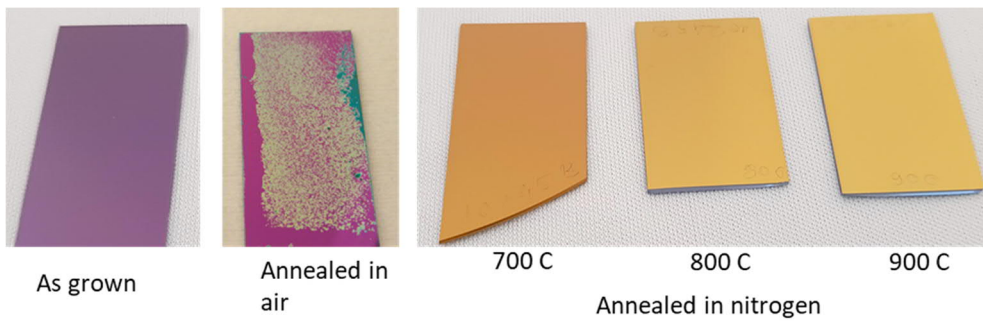


Figure 2. Optical picture of as deposited, annealed with presence of air and annealed in N₂ flow

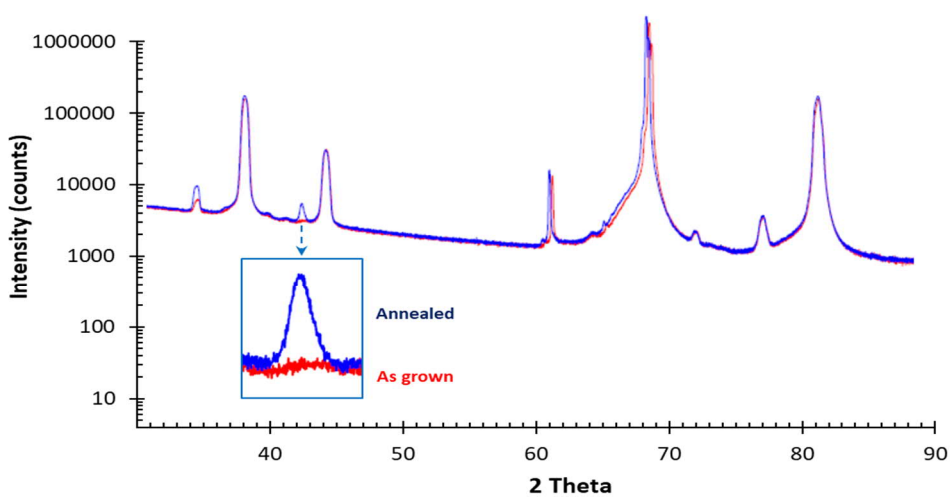


Figure 3. XRD spectra with appeared TiN (200) peak at $2\theta = 42.5^\circ$ after annealing.